

Special Issue

CFD Based Researches and Applications for Fluid Machinery and Fluid Device, Volume II

Message from the Guest Editors

This Special Issue on “CFD-Based Research and Applications for Fluid Machinery and Fluid Devices” aims to present recent novel research trends based on advanced CFD and experimental techniques for fluid machinery and fluid devices. The following topics, among others, are included in this issue:

- CFD and experimental techniques and applications in fluid machinery and fluid devices;
- Unsteady and transient phenomena in fluid machinery and fluid devices;
- Pumps, fans, compressors, hydraulic turbines, pump turbines, valves, etc.

Guest Editors

Dr. Jin-Hyuk Kim

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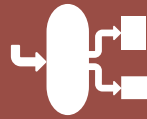
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Deadline for manuscript submissions

closed (20 December 2022)



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